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	Application No.	Applicant(s)	μ
	10/811,558	LEE ET AL.	
Notice of Allowability	Examiner	Art Unit	
	Sin J. Lee	1752	
The MAILING DATE of this communication apperature of the communication apperature of the series allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap) or other appropriate communicatio (IGHTS. This application is subject	oplication. If not included n will be mailed in due cou	ırse. THIS
1. This communication is responsive to <u>9/11/2006</u> .			
2. The allowed claim(s) is/are <u>1-6 and 13-16</u> .			
 Acknowledgment is made of a claim for foreign priority unally a) All b) □ Some* c) □ None of the: 	nder 35 U.S.C. § 119(a)-(d) or (f).		
 Certified copies of the priority documents have 	e been received.		
Certified copies of the priority documents have	e been received in Application No	<u> </u>	•
Copies of the certified copies of the priority do	cuments have been received in this	national stage application	from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:	•		
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requir	ements
 A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give 	nitted. Note the attached EXAMINER es reason(s) why the oath or declara	R'S AMENDMENT or NOT ation is deficient.	ICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftspers		-948) attached	
1) hereto or 2) to Paper No./Mail Date	:		
 (b) ☐ including changes required by the attached Examiner' Paper No./Mail Date 	's Amendment / Comment or in the	Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			ck) of
 DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT 			e the
Attachment(s)		•	
 Notice of References Cited (PTO-892) 	Notice of Informal F	Patent Application	
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ⊠ Interview Summary Paper No./Mail Da	ite <u>11/21/06</u> .	
 Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date 	7. 🛛 Examiner's Amend	ment/Comment	
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 	8. Examiner's Statem	ent of Reasons for Allowa	nce
	9. Other		
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EXAMINER'S AMENDMENT

1. Claims 7-12 and 17 are canceled claims.

- 2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.
- 3. Authorization for this examiner's amendment was given in a telephone interview with James P. Zeller (attorney for applicants) on November 21, 2006.
- 4. The application has been amended as follows:

In Claim 1, line 4, change "applying the organic" to --- applying an organic ---.
In Claim 16, line 1, change "claim 15" to --- claim 14 ---.

5. The following is an examiner's statement of reasons for allowance: As previously indicated, Neither Mitchell et al'137 nor Mougin'457 teaches or suggests present method of forming a pattern as claimed in present claim 1 or claim 13.

Although Hashino et al (JP 8-29972 and its machine-assisted English translation as provided by JPO) teaches a layer containing polyvinylphosphonic acid, in Hashino, the layer is applied on a support and then a photosensitive layer is applied on top of that layer. However, in present claims 1 and 13, a photoresist layer is first applied onto a semiconductor substrate, and then a layer containing polyvinylphosphonic acid is

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applied on top of the photoresist layer. Thus, Hashino et al (JP'972) does not teach or suggest present methods of claims 1 and 13.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sin J. Lee whose telephone number is 571-272-1333. The examiner can normally be reached on Monday-Friday from 9:00 am EST to 5:30 pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly, can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

November 21, 2006